AMENDMENTS TO THE CLAIMS

Below is the entire set of pending claims pursuant to 37 C.F.R §1.121(c)(3)(i), with any mark-ups showing the changes made by the present Amendment.

1. (Previously presented) A method for manufacturing an organic electroluminescent display, comprising:

forming a substantially transparent substrate;

forming a plurality of first display electrodes arranged in parallel on said substrate;

forming a non-photosensitive insulating layer over said substrate;

applying a cross-linking process to said non-photosensitive insulating layer;

forming a photosensitive insulating layer on said non-photosensitive insulating layer;

performing a photolithography process on said photosensitive insulating layer;

developing said photosensitive insulating layer and etching said non-photosensitive insulating layer so as to form a pattern of photosensitive insulating layer and non-photosensitive insulating layer having a shape with a longitudinal axis substantially perpendicular to a longitudinal axis of the first display electrodes, and the first display electrodes being exposed partly;

forming an organic electroluminescent material on the exposed first display electrodes; and

forming a plurality of second display electrodes on the organic electroluminescent material.

2. (Original) The method according to claim 1, wherein the non-photosensitive

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insulating layer is made of a thermal type polyimide.

- 3. (Original) The method according to claim 1, wherein the thickness of the non-photosensitive insulating layer is in a range of 0.5-2 µm.
- 4. (Previously presented) The method according to claim 1, wherein applying a cross-linking process to the non-photosensitive insulating layer comprises performing a baking process.
- 5. (Currently amended) The method according to claim 4, wherein the temperature of the baking process is in a range of about 120-180 Celsius degrees.
- 6. (Currently amended) The method according to claim 4, wherein the duration time of the baking process is in a range of about 20-60 minutes.
- (Currently amended) The method according to claim 1, wherein the thickness of the photosensitive insulating layer is in a range of about 3-5μm.
- 8. (Currently amended) The method according to claim 1, wherein the exposure to the photosensitive insulating layer during the photolithography process is in a range of about 30-80mJ/cm².
 - 9. (Previously presented) The method according to claim 1, wherein developing the

photosensitive insulating layer and etching the non-photosensitive insulating layer is proceeded through a developer solution.

- 10. (Previously presented) The method according to claim 9, wherein the developer solution is TMAH 2.38%.
- (Currently amended) The method according to claim 9, wherein the duration time for developing the photosensitive insulating layer and etching the non-photosensitive insulating layer is in a range of-about 50-100 seconds.
- 12. (Previously presented) The method according to claim 1, wherein the photosensitive insulating layer is developed into a reversed trapezoid shape.
- 13. (Previously presented) The method according to claim 12, wherein a long base of the reversed trapezoid shape of the photosensitive insulating layer is longer than or equal to a bottom edge of the shape of the etched non-photosensitive insulating layer.
- 14. (Previously presented) The method according to claim 1, wherein the non-photosensitive insulating layer is etched into a trapezoid shape.
- 15. (Previously presented) The method according to claim 14, wherein a top edge of the shape of the developed photosensitive insulating layer is longer than or equal to a long base of the trapezoid shape of the non-photosensitive insulating layer.

- 16. (Previously presented) The method according to claim 1, wherein developing the photosensitive insulating layer and etching the non-photosensitive insulating layer further comprises performing a curing process.
- 17. (Currently amended) The method according to claim 16, wherein the temperature of the curing process is in a range of about 200-350 Celsius degrees.
- 18. (Currently amended) The method according to claim 16, wherein the duration time of the curing process is in a range of about 30-120 minutes.
- 19. (Previously presented) A method for manufacturing an organic electroluminescent display, comprising:

forming a substantially transparent substrate;

forming a plurality of first display electrodes arranged in parallel on said substrate;

forming a non-photosensitive insulating layer over said substrate;

applying a baking process to said non-photosensitive insulating layer;

forming a photosensitive insulating layer on said non-photosensitive insulating layer, and pre-baking said photosensitive insulating layer;

performing a photolithography process on said photosensitive insulating layer so as to define a shape having a longitudinal axis perpendicular to a longitudinal axis of the first display electrodes, and performing a post-exposure baking process on said photosensitive insulating layer;

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dipping an aggregate composed of said substrate with said first display electrodes, said non-photosensitive insulating layer and said photosensitive insulating layer disposed thereon into a developer solution, whereby said photosensitive insulating layer is partially removed through development and said non-photosensitive insulating layer is partially removed by etching, and thereby said first display electrodes are exposed partially;

curing said aggregate;

forming an organic electroluminescent material on the exposed first display electrodes; and

forming a plurality of second display electrodes on the organic electroluminescent material.

- 20. (Original) The method according to claim 19, wherein the non-photosensitive insulating layer is made of a thermal type polyimide.
- 21. (Currently amended) The method according to claim 19, wherein the temperature of baking said non-photosensitive insulating layer is in a range of about 50-120 Celsius degrees.
- 22. (Currently amended) The method according to claim 19, wherein the temperature of post-exposure baking said photosensitive insulating layer is in a range of about 90-150 Celsius degrees.
- 23. (Currently amended) The method according to claim 19, wherein the duration time of post-exposure baking said photosensitive insulating layer is in a range of about 30-120

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- 24. (Previously presented) The method according to claim 19, wherein the photosensitive insulating layer is developed into a reversed trapezoid shape.
- 25. (Previously presented) The method according to claim 24, wherein a long base of the reversed trapezoid shape of the photosensitive insulating layer is longer than or equal to a bottom edge of the shape of the etched non-photosensitive insulating layer.
- 26. (Previously presented) The method according to claim 19, wherein the non-photosensitive insulating layer is etched into a trapezoid shape.
- 27. (Previously presented) The method according to claim 26, wherein a top edge of the shape of the developed photosensitive insulating layer is longer than or equal to a long base of the trapezoid shape of the non-photosensitive insulating layer.
- 28. (Previously presented) A method for manufacturing an organic electroluminescent display, comprising:

forming a substantially transparent substrate;

forming a plurality of first display electrodes arranged in parallel on said substrate;

forming a first photosensitive insulating layer over said substrate;

forming a second photosensitive insulating layer on said first photosensitive insulating layer;

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performing a photolithography process on said first and second photosensitive insulating layers;

developing said first and second photosensitive insulating layers simultaneously so as to form a pattern of first and second photosensitive insulating layers having a shape with a longitudinal axis substantially perpendicular to a longitudinal axis of the first display electrodes, and the first display electrodes being exposed partly;

forming an organic electroluminescent material on the exposed first display electrodes;

forming a plurality of second display electrodes on the organic electroluminescent material.

wherein the photosensitivity of the first photosensitive insulating layer is different from that of the second photosensitive insulating layer.

- 29. (Previously presented) The method according to claim 28, wherein developing said first and second photosensitive insulating layers is proceeded through a developer solution.
- 30. (Original) The method according to claim 28, wherein the photosensitivity of said first photosensitive insulating layer is greater than that of said second photosensitive insulating layer.
- 31. (Previously presented) A method for manufacturing an organic electroluminescent display, comprising:

forming a substantially transparent substrate;

and

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forming a plurality of first display electrodes arranged in parallel on said substrate;

forming a first photosensitive insulating layer over said substrate;

forming a second photosensitive insulating layer on said first photosensitive insulating layer;

performing a photolithography process on said first and second photosensitive insulating layers so as to define a shape having a longitudinal axis perpendicular to a longitudinal axis of the first display electrodes;

dipping an aggregate composed of said substrate with said first display electrodes, said first photosensitive insulating layer and said second photosensitive insulating layer disposed thereon into a developer solution, whereby said first and second photosensitive insulating layers are partially removed through development, and thereby said first display electrodes are exposed partially;

forming an organic electroluminescent material on the exposed first display electrodes;

forming a plurality of second display electrodes on the organic electroluminescent material.

- 32. (Original) The method according to claim 31, wherein the photosensitivity of said first photosensitive insulating layer is greater than that of said second photosensitive insulating layer.
- 33. (Currently amended) A method for manufacturing an electroluminescent display, comprising:

forming a first electrode on a <u>substantially transparent</u> substrate;

forming a non-photosensitive insulating layer to cover said first electrode;

forming a photosensitive insulating layer on said non-photosensitive insulating layer;

applying a photolithography process to said photosensitive insulating layer;

developing said photosensitive insulating layer and etching said non-photosensitive insulating layer using one same active solution to form a pattern of insulating material that partially exposes the first electrode;

forming an <u>organic</u> electroluminescent material on the exposed first electrode; and forming a second electrode on the <u>organic</u> electroluminescent material.

- 34. (Previously presented) The method according to claim 33, further comprising applying a cross-linking process to said non-photosensitive insulating layer.
- 35. (Currently amended) A method for manufacturing an electroluminescent display, comprising:

forming a first electrode on a <u>substantially transparent</u> substrate;

forming a non-photosensitive insulating layer to cover said first electrode;

applying a cross-linking process to said non-photosensitive insulating layer;

forming a photosensitive insulating layer on said non-photosensitive insulating layer;

applying a photolithography process to said photosensitive insulating layer;

developing said photosensitive insulating layer and etching said non-photosensitive insulating layer to form a pattern of insulating material that partially exposes the first electrode;

forming an <u>organic</u> electroluminescent material on the exposed first electrode; and

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forming a second electrode on the organic electroluminescent material.

36. (Currently amended) A method for manufacturing an electroluminescent display, comprising:

forming a first electrode on a substantially transparent substrate;

forming a first photosensitive insulating layer to cover said first electrode over said substrate;

forming a second photosensitive insulating layer on said first photosensitive insulating layer, wherein the photosensitivity of the first photosensitive insulating layer is different from that of the second photosensitive insulating layer;

applying a photolithography process to said first and second photosensitive insulating layers;

developing said first and second photosensitive insulating layers to form a pattern of insulating material that partially exposes the first electrode;

forming an <u>organic</u> electroluminescent material on the exposed first electrode; and · forming a second electrode on the <u>organic</u> electroluminescent material.